

**IN THE UNITED STATES PATENT AND TRADEMARK OFFICE**

In re patent application of

Jae-Jong HAN, et al.

Serial No.

*[Division of Serial No. 10/277,801, filed October 23, 2002]*

Filed: March 22, 2004

For: PLASMA ENHANCED CHEMICAL VAPOR DEPOSITION APPARATUS AND  
METHOD FOR FORMING NITRIDE LAYER USING THE SAME

**CONFIRMATION**  
**CLAIM FOR CONVENTION PRIORITY**

Commissioner for Patents  
Alexandria, VA 22313-1450

Sir:

The benefit of the filing date of the following prior foreign application filed in the following foreign country is hereby requested, and the right of priority provided in 35 U.S.C. §119 is hereby claimed:

**Application No. 2001-66104 - filed 25 October 2001 - Republic of Korea**

In support of this claim, a certified copy of said original foreign application was filed in parent application Serial No. 10/277,801 on October 23, 2002.

Acknowledgment of applicant's claim for priority and receipt of the certified priority document is solicited.

Respectfully submitted,

Date: March 22, 2004

  
Eugene M. Lee, Reg. No. 32,039

LEE & STERBA, P.C.  
1101 WILSON BOULEVARD, SUITE 2000  
ARLINGTON, VA 22209  
703.525.0978 TEL  
703.525.4265 FAX